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(Equivalent) Patent and Trademark Office

U.S. Application Serial No.
10/792,011

Atty. Docket No.
AM-5264.D1

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Cheng Guo et al.
Applicants

March 3, 2004
Filing Date

1756
Group



U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>SRM</u>	4,827,138	05/02/89	Randall *	250	492.2 R	
<u>SRM</u>	5,899,728	05/04/99	Mangat et al. *	438	459	
<u>SRM</u>	6,168,890	01/02/01	Takahashi *	430	5	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

SRM

S. D. Berger et al., "New approach to projection-electron lithography with demonstrated 0.1 μ m linewidth", Applied Physics Letters, Vol. 57, No. 2, pp. 153-155 (July 1990).

SRM

S. D. Berger et al., "Projection electron-beam lithography: A new approach", J. Vac. Sci. Technol. B, Vol. 9, No. 6, pp. 2996-2999 (Nov/Dec 1991).

Examiner

Date Considered

Mohamedolla

6/18/04

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

* Cited by the Examiner during the prosecution of the parent application, U.S. Serial No. 09/698,706.